PATENT ASSIGNMENT

Electronic Version v1.1 Stylesheet Version v1.1

SUBMISSION TYPE:	CORRECTIVE ASSIGNMENT	
NATURE OF CONVEYANCE:	Corrective Assignment to correct the Nature of Conveyance from an "Assignment" to "Security Agreement" previously recorded on Reel 026842 Frame 0929. Assignor(s) hereby confirms the the original document submitted was a "Security Agreement".	

CONVEYING PARTY DATA

Name	Execution Date
MOLECULAR IMPRINTS, INC.	09/01/2011

RECEIVING PARTY DATA

Name:	CANON INC.	
Street Address:	30-2 Shimomaruko 3-chome	
City:	Ohta-ku, Tokyo	
State/Country:	JAPAN	
Postal Code:	146-8501	

PROPERTY NUMBERS Total: 110

Property Type	Number
Patent Number:	7136150
Patent Number:	7140861
Patent Number:	7019835
Patent Number:	7785526
Patent Number:	7122079
Patent Number:	7323130
Patent Number:	7309225
Patent Number:	7105452
Patent Number:	7252715
Patent Number:	7036389
Patent Number:	6982783
Patent Number:	7244386
Patent Number:	7252777
	PATENT

PATENT

REEL: 031003 FRAME: 0031

Patent Number:	7041604
Patent Number:	7256131
Patent Number:	7282550
Patent Number:	7939131
Patent Number:	6990870
Patent Number:	7241395
Patent Number:	7547504
Patent Number:	7186656
Patent Number:	7205244
Patent Number:	7635445
Patent Number:	7292326
Patent Number:	7630067
Patent Number:	7798801
Patent Number:	7636999
Patent Number:	7170589
Patent Number:	7811505
Patent Number:	7281919
Patent Number:	7307118
Patent Number:	7298456
Patent Number:	7338275
Patent Number:	7727453
Patent Number:	7420654
Patent Number:	7316554
Patent Number:	7665981
Patent Number:	7387508
Patent Number:	7803308
Patent Number:	7259102
Patent Number:	7759407
Patent Number:	7670534
Patent Number:	7837921
Patent Number:	7279113
Patent Number:	7357876
Patent Number:	7906058
Patent Number:	7224443
Patent Number:	7037639
	PATENT

	7261831
Patent Number:	7906180
Patent Number:	7491637
Patent Number:	7691313
Patent Number:	7670529
Patent Number:	7670530
Patent Number:	7323417
Patent Number:	7635263
Patent Number:	7699598
Patent Number:	7780893
Patent Number:	7547398
Patent Number:	7462028
Patent Number:	7802978
Patent Number:	7854867
Patent Number:	7641840
Patent Number:	7473090
Patent Number:	6926929
Patent Number:	7670953
Patent Number:	7906274
Patent Number:	7837907
Patent Number:	6932934
Patent Number:	7845931
Patent Number:	7077992
Patent Number:	6900881
Patent Number:	7708926
Patent Number:	7795132
Patent Number:	6908861
Patent Number:	7071088
Patent Number:	7027156
Patent Number:	7070405
Patent Number:	6916584
Patent Number:	6936194
Patent Number:	6871558
Patent Number:	7785096
Patent Number:	7927541
<u>II</u>	PATENT

	6929762
Patent Number:	7019819
Patent Number:	7880872
Patent Number:	7874831
Patent Number:	6980282
Patent Number:	7931846
Patent Number:	7858528
Patent Number:	7132225
Patent Number:	7910042
Patent Number:	7943081
Patent Number:	7452574
Patent Number:	7947608
Patent Number:	6805054
Patent Number:	7179396
Patent Number:	7396475
Patent Number:	6951173
Patent Number:	7442336
Patent Number:	7179079
Patent Number:	7150622
Patent Number:	7531025
Patent Number:	7270533
Patent Number:	7768624
Patent Number:	7815824
Patent Number:	7261830
Patent Number:	7090716
Patent Number:	7157036
Patent Number:	7122482

CORRESPONDENCE DATA

2128016400 Fax Number:

Correspondence will be sent via US Mail when the fax attempt is unsuccessful.

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Correspondent Name: Shoba Jaglal Address Line 1: 200 Park Avenue, Greenberg Traurig, LLP Address Line 2: New York, NEW YORK 10166 Address Line 4:

PATENT

REEL: 031003 FRAME: 0034

	093155.010200
NAME OF SUBMITTER:	Shoba Jaglal
Signature:	/sjaglal/
Date:	08/13/2013
Total Attachments: 31	
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COLLATERAL ASSIGNMENT OF PATENT AGREEMENT

- THIS COLLATERAL ASSIGNMENT OF PATENT AGREEMENT ("Assignment"), dated as of September 1, 2011, made by and between MOLECULAR IMPRINTS, INC., a Delaware corporation ("Assignor"), and CANON INC., a Japanese corporation ("Assignee").
- WHEREAS, Assignor and Assignee are parties to that certain Term Loan Agreement dated as of August 9, 2011 (as same may be amended, modified, supplemented and/or restated from time to time, the "Loan Agreement"); and Assignor and Assignee are parties to that certain Collateral Agreement, dated as of August 9, 2011 (as same may be amended, modified, supplemented and/or restated from time to time, the "Collateral Agreement"). Capitalized terms used but not defined herein shall have the meanings given to them in the Loan Agreement.
- WHEREAS, pursuant to the Loan Agreement, Assignee has agreed to make a loan to Assignor upon the terms and subject to the conditions set forth in the Loan Agreement; and pursuant to the Collateral Agreement, Assignee has granted a security interest in certain of its assets, including all patents and patent applications, to secure the Obligations.
- WHEREAS, it is a condition to the obligation of the Assignee to make the loan to Assignor under the Loan Agreement, that Assignor shall have executed and delivered this Assignment.
- **NOW, THEREFORE**, in order to induce Assignee to make the loan, for one dollar in hand paid to Assignor, and other good and valuable consideration, the receipt and sufficiency of which is hereby acknowledged by Assignor, Assignor and Assignee hereby agree as follows:
- 1. As collateral security for the prompt and complete payment and performance when due (whether at the stated maturity, by acceleration or otherwise) of the Obligations (as defined in the Loan Agreement), Assignor does hereby grant and assign to Assignee all of its right, title and interest in and to the United States patents and patent applications listed on the annexed Schedule A, all inventions covered thereby, all re-issue, division, continuation, continuation-in-part, renewal and extension patents and all rights corresponding thereto throughout the world, including all of Assignor's rights under the International Convention (hereinafter individually or collectively, "Patents"), and all of Assignor's right, title and interest in any causes of action or rights of recovery that Assignor may have for any past infringement of the Patents. Assignor acknowledges and represents that Schedule A annexed hereto lists all of the United States patents and patent applications that are owned or controlled by Assignor or its Affiliates.
- 2. Until written notice of revocation by Assignee to Assignor after the occurrence and during the existence of an Event of Default, Assignee hereby grants to Assignor the exclusive right and license (to the exclusion of any right of the Assignee):
- a. To make, have made, use and sell throughout the world the inventions covered by the Patents;

NY 241,058,370v5

- b. To prosecute, maintain, defend and enforce, and to commence and control the prosecution and defense of any action or proceeding relating to, the Patents in the United States Patent and Trademark Office or before any foreign patent office or before any Court or other judicial or quasi-judicial body, solely in Assignor's own name;
- c. To settle or compromise any action or proceeding brought or commenced in the United States Patent and Trademark Office or in any foreign patent office, or before any Court or other judicial or quasi-judicial body, involving or relating to any Patents, without the prior consent or approval of Assignee, including without limitation any action involving the infringement, validity or enforceability of the Patents, or any interference or other Patent and Trademark Office proceedings or other Patent and Trademark Office proceedings relating to the Patents;
- d. To recover for all past, present and future infringements of the Patents, including without limitation all damages, costs and attorneys' fees relating thereto;
- e. To receive all license royalties or other consideration related to the Patents;
- f. To have any applications for Patents that are pending as of the effective date of this Assignment issue solely in the name of Assignor (and not, for the avoidance of doubt, issue in the name of Assignee notwithstanding the assignment set forth in Section 1 hereof); and
- g. To maintain, including without limitation the payment of all maintenance, annuity or renewal fees, all Patent rights unless Assignor shall have received prior written consent of Assignee's abandonment.
- 3. Upon request by Assignor, Assignee agrees to execute such documents and to cooperate with Assignor as may reasonably be necessary in connection with the prosecution, maintenance, defense and enforcement of the Patents and to effect the licenses granted to Assignor by Section 2.
- 4. Until written notice of revocation by Assignee after the occurrence and during the existence of an Event of Default, Assignee hereby grants to Assignor a Power of Attorney with full power of substitution and revocation, including a power to appoint attorneys and associate attorneys, and to revoke their powers, to file, and assent to the filing of, prosecute, amend, alter and receive Letters Patent in Assignor's own name (including without limitation reissue patents), and to transact any and all business in the United States Patent and Trademark Office or before any foreign patent office or before any other judicial or quasi-judicial body, relating to the Patents.
- 5. Upon the occurrence and during the existence of an Event of Default, Assignor's exclusive rights and licenses granted under Section 2 hereof shall be subject to Assignee's rights and remedies under the Collateral Agreement and other applicable agreements and those rights and remedies granted to a secured party under the Uniform Commercial Code, as enacted in any jurisdiction in which the Patents may be located.

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- 6. Assignor warrants that it holds unencumbered title to the Patents, subject to this Assignment. Assignor agrees not to sell, assign or encumber its interest in, or grant any license with respect to, the Patents without the prior written consent of Assignee, except as permitted under the Loan Agreement. Any attempted sale, assignment or encumbrance not made by Assignor in accordance with this Section 6 shall be void.
- 7. If Assignor should obtain rights to, or become entitled to the benefit of, any reissue, division, continuation, continuation-in-part, renewal or extension patents or patent applications for the Patents, Assignor shall give Assignee prompt written notice thereof to Assignee or as otherwise contemplated by the Collateral Agreement and the provisions of this Assignment shall automatically apply thereto.
- 8. Nothing herein shall be construed or deemed to grant to Assignee any express or implied right, title or interest in or to any patent or patent application of Assignor other than the Patents as expressly enumerated herein, other than as necessary to practice the inventions patented by the Patents.
- 9. Prior to the occurrence of an Event of Default, Assignee covenants and agrees that it shall not (a) sell, assign, transfer or convey to any third party, or otherwise encumber, any right, title or interest it may have in the Patents, or (b) otherwise interfere with any of Assignor's exclusive rights and licenses granted hereunder.
- 10. At such time as the Obligations (other than any indemnification or similar obligation that survives the termination of the Loan Agreement or the Collateral Agreement and as to which no claim is then pending) shall have been indefeasibly paid in full, all right, title and interest granted by Assignor to Assignee herein shall immediately and automatically revert and transfer back to Assignor. Assignee agrees to cooperate with Assignor and to execute such documents upon request as may reasonably be necessary to formalize and record such reversion and transfer back.
- 11. This Assignment shall inure to the benefit of and be binding upon the respective successors and permitted assigns of the parties.

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IN WITNESS WHEREOF, Assignor and Assignee have executed this instrument.

MOLECULAR IMPRINTS, INC.	CANON INC.
- Tale on ANDS-	
Ву: ///////	By:
Name: <u>7AVID S. 6M0</u>	Name:
Title: <u>Coo/CFo</u>	Title:

Collateral Assignment of Patent Agreement

IN WITNESS WHEREOF, Assignor and Assignee have executed this instrument.

MOLECULAR IMPRINTS, INC.	CANON INC.
By:	By: Tennis Nepska
Name:	Name: Tsuneji Øchida
Title:	Title: President & COO

Collateral Assignment of Patent Agreement

SCHEDULE A

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
		Imprint Lithography Template	
		Having Opaque Alignment	
7,136,150	14-Nov-2006	Marks	Sreenivasan, Sidlgata V.; Schumaker, Philip D.
		Compliant Hard Template for	Watts, Michael P.C.; Voisin, Ronald D.;
7,140,861	28-Nov-2006	UV Imprinting	Sreenivasan, Sidlgata V.
		Method and System to Measure	McMackin, Ian Matthew; Schumaker, Philip
		Characteristics of a Film	D.; Choi, Byung-Jin; Sreenivasan, Sidlgata V.;
7,019,835	28-Mar-2006	Disposed on a Substrate	Watts, Michael P.C.
		Imprint Alignment Method,	
7,785,526	31-Aug-2010	System and Template	Voisin, Ronald D.
1,100,020	011108 2010	Composition for an Etching	, otoni, remain 21
		Mask Comprising a Silicon-	Xu, Frank Y.; Miller, Michael N.; Watts,
7,122,079	17-Oct-2006	Containing Material	Michael P.C.
7,122,077	17 000 2000	Magnification Correction	Nimmakayala, Pawan Kumar; Sreenivasan,
		Employing Out-Of-Plane	Sidlgata V.; Choi, Byung-Jin; Cherala,
7,323,130	29-Jan-2008	Distortion of a Substrate	Anshuman
192629120	27-Jan-2000		/ XEDIGITIAL
7 200 225	10 D 2007	Moat system for an imprint	M-M-dia I. M-mb I. J. Dadai D
7,309,225	18-Dec-2007	lithography template	McMackin, Ian Matthew; Lad, Pankaj B.
		Method Of Planarizing A	
		Semiconductor Substrate with	
7.105.450	10.5 0006	an Etching Chemistry (as	0 ' 0'11 ' 17
7,105,452	12-Sep-2006	amended)	Sreenivasan, Sidlgata V.
			Watts, Michael P.C.; Choi, Byung-Jin;
7,252,715	07-Aug-2007	System for Dispensing Liquids	Sreenivasan, Sidlgata V.
		System for Determining	
		Characteristics of Substrates	
7,036,389	02-May-2006	Employing Fluid Geometries	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
			Choi, Byung-Jin; Voisin, Ronald D.;
		Chucking System for	Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
		Modulating Shapes of	Babbs, Daniel A.; Meissl, Mario Johannes;
6,982,783	03-Jan-2006	Substrates	Bailey, Hillman L.; Schumaker, Norman E.
		Method of Compensating for a	
		Volumetric Shrinkage of a	
		Material Disposed upon a	
		Substrate to Form a	
		Substantially Planar Structure	
7,244,386	17-Jul-2007	Therefrom	Sreenivasan, Sidlgata V.; Xu, Frank Y.
		Method of Forming an In-situ	Vidusek, David; Sreenivasan, Sidlgata V.;
7,252,777	07-Aug-2007	Recessed Structure	Wang, David C.
		Method of Patterning Surfaces	
		While Providing Greater	
		Control of Recess Anisotropy	
7,041,604	09-May-2006	(as amended)	Miller, Michael N.; Stacey, Nicholas A.
		Method of Controlling the	
		Critical Dimension of	
		Structures Formed on a	
7,256,131	14-Aug-2007	Substrate	LaBrake, Dwayne L.
1 3 200 0 3 1 0 1	11.116 2007	Composition To Provide A	2000 2000 to 11 to y 220 Add
		Layer With Uniform Etch	
7,282,550	16-Oct-2007	Characteristics	Xu, Frank Y.; Stacey, Nicholas A.
194049220	10-001-2007	1 Characteristics	1 226, 1 mile 1., butty, Premons A.

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
			Xu, Frank Y.; Mackay, Christopher J.; Lad,
			Pankaj B.; McMackin, Ian Matthew; Truskett,
		Method To Provide A Layer	Van Nguyen; Martin, Wesley; Fletcher, Edward
		With Uniform Etch	B.; Wang, David C.; Stacey, Nicholas A.;
7,939,131	10-May-2011	Characteristics	Watts, Michael P.C.
		System for Determining	
		Characteristics of Substrates	
6,990,870	31-Jan-2006	Employing Fluid Geometries	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
		Reverse Tone Patterning on	
		Surfaces Having Surface	
7,241,395	10-Jul-2007	Planarity Perturbations	Sreenivasan, Sidlgata V.; Stacey, Nicholas A.
		Pattern Reversal Employing	
7,547,504	16-Jun-2009	Thick Residual Layers	Sreenivasan, Sidlgata V.
		Method of Forming a Recessed	
	0.00	Structure Employing a Reverse	
7,186,656	06-Mar-2007	Tone Process	Sreenivasan, Sidlgata V.
		Patterning Substrates	
		Employing Multi-Film Layers	C. NI I I A C. C. C. II A A
7.005.044	17 4 2007	Defining Etch Differential	Stacey, Nicholas A.; Sreenivasan, Sidlgata V.;
7,205,244	17-Apr-2007	Interfaces	Miller, Michael N.
			Choi, Byung-Jin; Cherala, Anshuman; Choi,
		Mathada of Caranating a Mald	Yeong-jun; Meissl, Mario Johannes;
		Methods of Separating a Mold from a Solidified Layer	Sreenivasan, Sidlgata V.; Schumaker, Norman E.; Lu, Xiaoming; McMackin, Ian Matthew;
7,635,445	22-Dec-2009	Disposed on a Substrate	Babbs, Daniel A.
1,033,443	22-DCC-2009	Interferometric Analysis for the	Nimmakayala, Pawan Kumar; Rafferty, Tom
		Manufacture of Nano-Scale	H.; Aghili, Alireza; Choi, Byung-Jin;
7,292,326	06-Nov-2007	Devices	Schumaker, Philip D.; Babbs, Daniel A.
1,20,20,20	00 1107 2007	2000	Nimmakayala, Pawan Kumar; Rafferty, Tom
		Interferometric Analysis	H.; Aghili, Alireza; Choi, Byung-Jin;
		Method for the Manufacture of	Schumaker, Philip D.; Babbs, Daniel A.;
7,630,067	08-Dec-2009	Nano-Scale Devices	Truskett, Van Nguyen
		Chucking System for Nano-	Babbs, Daniel A.; Choi, Byung-Jin; Cherala,
7,798,801	21-Sep-2010	Manufacturing	Anshuman
		Method of Retaining a	Choi, Byung-Jin; Cherala, Anshuman; Babbs,
7,636,999	29-Dec-2009	Substrate to a Wafer Chuck	Daniel A.
		Apparatus to Vary Dimensions	Cherala, Anshuman; Choi, Byung-Jin;
		of a Substrate During Nano-	Nimmakayala, Pawan Kumar; Meissl, Mario
7,170,589	30-Jan-2007	Scale Manufacturing	Johannes; Sreenivasan, Sidlgata V.
		Method For Fast Filling Of	
		Templates For Imprint	
		Lithography Using On	McMackin, Ian Matthew; Lad, Pankaj B.;
7,811,505	12-Oct-2010	Template Dispense	Truskett, Van Nguyen
			Shackleton, Steven C; McMackin, Ian
		System for Controlling a	Matthew; Lad, Pankaj B.; Truskett, Van
7,281,919	16-Oct-2007	Volume of Material on a Mold	Nguyen
		Composition to Reduce	
		Adhesion between a	
		Conformable Region and a	
7,307,118	11-Dec-2007	Mold	Xu, Frank Y.; Miller, Michael N.
		System for Varying Dimensions	Cherala, Anshuman; Choi, Byung-Jin;
T 200 455		of a Substrate During	Nimmakayala, Pawan Kumar; Meissl, Mario
7,298,456	20-Nov-2007	Nanoscale Manufacturing	Johannes; Sreenivasan, Sidlgata V.

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
		Formation of Discontinuous	
		Films During an Imprint	Choi, Byung-Jin; Sreenivasan, Sidlgata V.;
7,338,275	04-Mar-2008	Lithography Process	Meissl, Mario Johannes; Watts, Michael P.C.
			Sreenivasan, Sidlgata V.; Choi, Byung-Jin;
		Step and Repeat Imprint	Schumaker, Norman E.; Voisin, Ronald D.;
7,727,453	01-Jun-2010	Lithography Processes	Watts, Michael P.C.; Meissl, Mario Johannes
		Method of Varying Dimensions	Cherala, Anshuman; Choi, Byung-Jin;
		of a Substrate During Nano-	Nimmakayala, Pawan Kumar; Meissl, Mario
7,420,654	02-Sep-2008	Scale Manufacturing	Johannes; Sreenivasan, Sidlgata V.
.,,		System to Control an	
		Atmosphere between a Body	
7,316,554	08-Jan-2008	and a Substrate	Choi, Yeong-jun; Choi, Byung-Jin
7,310,334	00-7411-2000	System to Transfer a Template	Choi, 1 cong-jan, Choi, Dyung-vin
		Transfer Body between a	
			Cohamatan Bhilin D. Fancella Amada Vin
7.665.001	22 5-1- 2010	Motion Stage and a Docking	Schumaker, Philip D.; Fancello, Angelo; Kim,
7,665,981	23-Feb-2010	Plate	Jae H.; Choi, Byung-Jin; Babbs, Daniel A.
		Compliant Device for Nano-	
7,387,508	17-Jun-2008	Scale Manufacturing	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
		Technique for Separating a	GanapathiSubramanian, Mahadevan; Choi,
		Mold from Solidified	Byung-Jin; Miller, Michael N.; Stacey,
7,803,308	28-Sep-2010	Imprinting Material	Nicholas A.
		Etching Technique to Planarize	
7,259,102	21-Aug-2007	a Multi-Layer Structure	Wang, David C.; Xu, Frank Y.
······································		Composition for Adhering	
7,759,407	20-Jul-2010	Materials Together	Xu, Frank Y.
7,722,137	1000000	Method to Control an	1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1
		Atmosphere Between a Body	
7,670,534	02-Mar-2010	and a Substrate	Choi, Yeong-jun; Choi, Byung-Jin
7,070,554	02-14141-2010	Method of Providing Desirable	Choi, 1 Cong-jan, Choi, Dyung-thi
		Wetting and Release	
		Characteristics Between a Mold	Xu, Frank Y.; Lad, Pankaj B.; McMackin, Ian
7 027 021	22 Nov. 2010	and a Polymerizable	Matthew; Truskett, Van Nguyen; Fletcher, Edward B.
7,837,921	23-Nov-2010	Composition	Edward B.
		A Method of Forming a	Www.vc.t lb.C.V.; b. 115
7.070.112	00.0.4.2007	Compliant Template for UV	Watts, Michael P.C.; Voisin, Ronald D.;
7,279,113	09-Oct-2007	Imprinting	Sreenivasan, Sidlgata V.
		Eliminating Printability of Sub-	
	1.5.1.2000	Resolution Defects in Imprint	0.11
7,357,876	15-Apr-2008	Lithography	Sreenivasan, Sidlgata V.
		1	GanapathiSubramanian, Mahadevan; Choi,
		Bifurcated Contact Printing	Byung-Jin; Miller, Michael N.; Stacey,
7,906,058	15-Mar-2011	Technique	Nicholas A.; Watts, Michael P.C.
			Choi, Byung-Jin; Voisin, Ronald D.;
		Imprint Lithography Substrate	Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
		Processing Tool for Modulating	Babbs, Daniel A.; Meissl, Mario Johannes;
7,224,443	29-May-2007	Shapes of Substrates	Bailey, Hillman L.; Schumaker, Norman E.
		Methods of Manufacturing a	
7,037,639	02-May-2006	Lithography Template	Voisin, Ronald D.
		Positive Tone Bi-Layer Imprint	
7,261,831	28-Aug-2007	Lithography Method	Sreenivasan, Sidlgata V.
1500150011	20-11ug-2001	Composition for an Etching	Groomvasan, Gargara v.
		Mask Comprising a Silicon-	Yn Frank V : Miller Michael N : Wette
7 006 190	15 Mar 2011		Xu, Frank Y.; Miller, Michael N.; Watts,
7,906,180	15-Mar-2011	Containing Material	Michael P.C.

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
		Formation of Conductive	
		Templates Employing Indium	Sreenivasan, Sidlgata V.; McMackin, Ian
7,491,637	17-Feb-2009	Tin Oxide	Matthew; Choi, Byung-Jin; Voisin, Ronald D.
		Method for Expelling Gas	
		Positioned Between a Substrate	Choi, Byung-Jin; Sreenivasan, Sidlgata V.;
7,691,313	06-Apr-2010	and a Mold	McMackin, lan Matthew; Lad, Pankaj B.
		Method and System for	
		Double-Sided Patterning of	
7,670,529	02-Mar-2010	Substrates	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
		Patterning Substrates	
7,670,530	02-Mar-2010	Employing Multiple Chucks	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
		Method of Forming a Recessed	
		Structure Employing a Reverse	
7,323,417	29-Jan-2008	Tone Process	Sreenivasan, Sidlgata V.
		Chucking System Comprising	Cherala, Anshuman; Choi, Byung-Jin; Lad,
7,635,263	22-Dec-2009	an Array of Fluid Chambers	Pankaj B.; Shackleton, Steven C
		Conforming Template for	
		Patterning Liquids Disposed on	Sreenivasan, Sidlgata V.; Choi, Byung-Jin;
7,699,598	20-Apr-2010	Substrates	Voisin, Ronald D.
	-	Method of concurrently	
		patterning a substrate having a	Sreenivasan, Sidlgata V.; McMackin, Ian
		plurality of fields and a	Matthew; Melliar-Smith, Christopher M.; Choi,
7,780,893	24-Aug-2010	plurality of alignment marks	Byung-Jin
		Self-Aligned Process for	
		Fabricating Imprint Templates	Schmid, Gerard M.; Stacey, Nicholas A.;
		Containing Variously Etched	Resnick, Douglas J.; Voisin, Ronald D.; Myron
7,547,398	16-Jun-2009	Features	Lawrence J.
		Partial Vacuum Environment	Cherala, Anshuman; Lad, Pankaj B.;
7,462,028	09-Dec-2008	Imprinting	McMackin, Ian Matthew; Choi, Byung-Jin
		Imprinting of Partial Fields at	
7,802,978	28-Sep-2010	the Edge of the Wafer	Sreenivasan, Sidlgata V.; Choi, Byung-Jin
		Method for Detecting a Particle	
		in a Nanoimprint Lithography	
7,854,867	21-Dec-2010	System	Schumaker, Philip D.
		METHOD FOR EXPELLING	
		GAS POSITIONED	Choi, Byung-Jin; GanapathiSubramanian,
		BETWEEN A SUBSTRATE	Mahadevan; Choi, Yeong-jun; Meissl, Mario
7,641,840	05-Jan-2010	AND A MOLD	Johannes
		Imprint Lithography Template	
		to Facilitate Control of Liquid	McMackin, Ian Matthew; Lad, Pankaj B.;
7,473,090	06-Jan-2009	Movement	Truskett, Van Nguyen
		System and Method For	Watts, Michael P.C.; Choi, Byung-Jin;
6,926,929	09-Aug-2005	Dispensing Liquids	Sreenivasan, Sidlgata V.
7,670,953	02-Mar-2010	Positive Tone Bi-Layer Method	Sreenivasan, Sidlgata V.
7 7		Method of Creating a Template	Schmid, Gerard M.; Resnick, Douglas J.;
7,906,274	15-Mar-2011	Employing a Lift-Off Process	Miller, Michael N.
, , -		Alignment System and Method	
		for a Substrate in a Nano-	
7,837,907	23-Nov-2010	Imprint Process	Nimmakayala, Pawan Kumar; Choi, Byung-Jin
		Formation of Discontinuous	
		Films During an Imprint	Choi, Byung-Jin; Meissl, Mario Johannes;
6,932,934	23-Aug-2005	Lithography Process	Sreenivasan, Sidlgata V.; Watts, Michael P.C.
7,845,931	07-Dec-2010		
1,043,731	107-DCC-2010	Polymerization Technique to	Xu, Frank Y.; Fletcher, Edward B.; Lad, Panka

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
		Attenuate Oxygen Inhibition of	B.; Watts, Michael P.C.
		Solidification of Liquids and	
		Composition Therefor	
			Sreenivasan, Sidlgata V.; Choi, Byung-Jin;
		Step and Repeat Imprint	Schumaker, Norman E.; Voisin, Ronald D.;
7,077,992	18-Jul-2006	Lithography Process	Watts, Michael P.C.; Meissl, Mario Johannes
			Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
		Step and Repeat Imprint	Choi, Byung-Jin; Meissl, Mario Johannes;
6,900,881	31-May-2005	Lithography Systems	Schumaker, Norman E.; Voisin, Ronald D.
7,708,926	04-May-2010	Capillary Imprinting Technique	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
		Self-Aligned Cross-Point	Sreenivasan, Sidlgata V.; Melliar-Smith,
7,795,132	14-Sep-2010	Memory Fabrication	Christopher M.; LaBrake, Dwayne L.
		Method for Imprint	
		Lithography Using an Electric	Sreenivasan, Sidlgata V.; Bonnecaze, Roger T.;
6,908,861	21-Jun-2005	Field	Willson, Carlton Grant
		Method for Fabricating	
7,071,088	04-Jul-2006	Bulbous-Shaped Vias	Watts, Michael P.C.; Sreenivasan, Sidlgata V.
	***************************************	Scatterometry Alignment for	<u> </u>
7,027,156	11-Apr-2006	Imprint Lithography	Watts, Michael P.C.; McMackin, Ian Matthew
	1		Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
		Alignment Systems for Imprint	Choi, Byung-Jin; Voisin, Ronald D.;
7,070,405	04-Jul-2006	Lithography	Schumaker, Norman E.
,,o,o,	0.0012000	Alignment Methods for Imprint	Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
6,916,584	12-Jul-2005	Lithography	Choi, Byung-Jin; Voisin, Ronald D.
0,210,207	12 341 2005	Functional Patterning Material	Choi, Dyung sin, Voisin, Ronaid D.
		For Imprint Lithography	
6,936,194	30-Aug-2005	Processes	Watts, Michael P.C.
0,230,121	30 7145 2005	Method for Determining	muss, micraet i.e.
		Characteristics of Substrates	
6,871,558	29-Mar-2005	Employing Fluid Geometries	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
3,0,71,000	2000	Enhanced Multi Channel	Nimmakayala, Pawan Kumar; Choi, Byung-Jin;
7,785,096	31-Aug-2010	Alignment	Rafferty, Tom H.; Schumaker, Philip D.
7,7,00,00		Full-Wafer or Large Area	
		Imprinting with Multiple	
		Separated Sub-Fields for High	
7,927,541	19-Apr-2011	Throughput Lithography	Sreenivasan, Sidlgata V.
	····	Method of Reducing Pattern	
		Distortions During Imprint	
6,929,762	16-Aug-2005	Lithography Processes	Rubin, Daniel I.
······			Choi, Byung-Jin; Voisin, Ronald D.;
		Chucking System for	Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
		Modulating Shapes of	Babbs, Daniel A.; Meissl, Mario Johannes;
7,019,819	28-Mar-2006	Substrates	Bailey, Hillman L.; Schumaker, Norman E.
			Nimmakayala, Pawan Kumar; Rafferty, Tom
		Interferometric Analysis	H.; Aghili, Alireza; Choi, Byung-Jin;
		Method for the Manufacture of	Schumaker, Philip D.; Babbs, Daniel A.;
7,880,872	01-Feb-2011	Nano-Scale Devices	Truskett, Van Nguyen
		Template Having a Silicon	
		Nitride, Silicon Carbide or	Resnick, Douglas J.; Meissl, Mario Johannes;
7,874,831	25-Jan-2011	Silicon Oxynitride Film	Selinidis, Kosta S.; Xu, Frank Y.
			Choi, Byung-Jin; Voisin, Ronald D.;
		Method for Modulating Shapes	Sreenivasan, Sidlgata V.; Watts, Michael P.C.;
6,980,282	27-Dec-2005	of Substrates	Willson, Carlton Grant; Schumaker, Norman

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
			E.; Meissl, Mario Johannes
		Method to Control an	
		Atmosphere Between a Body	
7,931,846	26-Apr-2011	and a Substrate	Choi, Yeong-jun; Choi, Byung-Jin
7,858,528	28-Dec-2010	Positive Tone Bi-Layer Method	Sreenivasan, Sidlgata V.
		Methods of Inspecting a	
7,132,225	07-Nov-2006	Lithography Template	Voisin, Ronald D.
7,910,042	22-Mar-2011	Capillary Imprinting Technique	Choi, Byung-Jin; Sreenivasan, Sidlgata V.
			Sreenivasan, Sidlgata V.; Choi, Byung-Jin;
		Step and Repeat Imprint	Schumaker, Norman E.; Voisin, Ronald D.;
7,943,081	17-May-2011	Lithography Processes	Watts, Michael P.C.; Meissl, Mario Johannes
		Method to Reduce Adhesion	
		Between a Polymerizable Layer	
5 150 CT 4	10.37 0000	and a Substrate Employing a	Truskett, Van Nguyen; Mackay, Christopher J.;
7,452,574	18-Nov-2008	Fluorine-Containing Layer	Choi, Byung-Jin
7,947,608	24-May-2011	Positive Tone Bi-Layer Method	Sreenivasan, Sidlgata V.
		Method, System and Holder for	
6.00%.054	10.0 + 2004	Transferring Templates During	Meissl, Mario Johannes; Choi, Byung-Jin;
6,805,054	19-Oct-2004	Imprint Lithography Processes	Babbs, Daniel A.; Bailey, Hillman L.
7,179,396	20-Feb-2007	Positive Tone Bi-Layer Imprint Lithography Method	Sreenivasan, Sidlgata V.
7,179,390	20-160-2007	Method of Forming Stepped	Steemvasan, Sinigata V.
		Structures Employing Imprint	
7,396,475	08-Jul-2008	Lithography	Sreenivasan, Sidlgata V.
7,550,170	00 (41 2000	Assembly and Method for	Divisional, Statement 1
		Transferring Imprint	
6,951,173	04-Oct-2005	Lithography Templates	Meissl, Mario Johannes; Choi, Byung-Jin
			Choi, Byung-Jin; Sreenivasan, Sidlgata V.;
7,442,336	28-Oct-2008	Capillary Imprinting Technique	Watts, Michael P.C.
		Conforming Template for	
		Patterning Liquids Disposed on	Sreenivasan, Sidlgata V.; Choi, Byung-Jin;
7,179,079	20-Feb-2007	Substrates	Voisin, Ronald D.
		Systems for Magnification and	
7.150.600	10 D 2006	Distortion Correction for	Choi, Byung-Jin; Sreenivasan, Sidlgata V.;
7,150,622	19-Dec-2006	Imprint Lithography Processes	Meissl, Mario Johannes
		Method for Creating A Turbulent Flow Of Fluid	McMackin, Ian Matthew; Stacey, Nicholas A.; Babbs, Daniel A.; Voth, Duane; Watts, Michael
		Between A Mold And A	P.C.; Truskett, Van Nguyen; Xu, Frank Y.;
7,531,025	12-May-2009	Substrate	Voisin, Ronald D.; Lad, Pankaj B.
195019010	12 11111 2005	System for Creating a	McMackin, Ian Matthew; Stacey, Nicholas A.;
		Turbulent Flow of Fluid	Babbs, Daniel A.; Voth, Duane; Watts, Michael
		Between a Mold and a	P.C.; Truskett, Van Nguyen; Xu, Frank Y.;
7,270,533	18-Sep-2007	Substrate	Voisin, Ronald D.; Lad, Pankaj B.
		METHOD FOR OBTAINING	
		FORCE COMBINATIONS	
		FOR TEMPLATE	
		DEFORMATION USING	
		NULLSPACE AND	Chamle Anchomen Consider St. M.
7,768,624	03-Aug-2010	METHODS OPTIMIZATION TECHNIQUES	Cherala, Anshuman; Sreenivasan, Sidlgata V.; Choi, Byung-Jin; Thompson, Ecron D.
1,100,024	05-Aug-2010	REAL TIME IMPRINT	Choi, Dyang-Jin, Thompson, ECIOH D.
		PROCESS DIAGNOSTICS	Sreenivasan, Sidlgata V.; Singhal, Shrawan;
7,815,824	19-Oct-2010	FOR DEFECTS	Choi, Byung-Jin

PATENT NO.	ISSUE DATE	TITLE	INVENTORS
		Applying Imprinting Material	
		to Substrates Employing	Cherala, Anshuman; Sreenivasan, Sidlgata V.;
7,261,830	28-Aug-2007	Electromagnetic Fields	Schumaker, Norman E.
			McMackin, lan Matthew; Stacey, Nicholas A.;
			Babbs, Daniel A.; Voth, Duane; Watts, Michael
		Single Phase Fluid Imprint	P.C.; Truskett, Van Nguyen; Xu, Frank Y.;
7,090,716	15-Aug-2006	Lithography Method	Voisin, Ronald D.; Lad, Pankaj B.
		Method to Reduce Adhesion	Choi, Byung-Jin; Xu, Frank Y.; Stacey,
		Between a Conformable Region	Nicholas A.; Truskett, Van Nguyen; Watts,
7,157,036	02-Jan-2007	and a Pattern of a Mold	Michael P.C.
		Methods for Fabricating	
		Patterned Features Utilizing	Xu, Frank Y.; Stacey, Nicholas A.; Watts,
7,122,482	17-Oct-2006	Imprint Lithography	Michael P.C.; Thompson, Ecron D.

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MOLECULAR IMPRINTS, INC. DOC DATE: 09/01/2011

ASSIGNEE:

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APPLICATION NUMBER: 10670980 FILING DATE: 09/25/2003 PATENT NUMBER: 7136150 ISSUE DATE: 11/14/2006 TITLE: IMPRINT LITHOGRAPHY TEMPLATE HAVING OPAQUE ALIGNMENT MARKS

APPLICATION NUMBER: 10833240 FILING DATE: 04/27/2004 PATENT NUMBER: 7140861 FILING DATE: 11/28/2006

TITLE: COMPLIANT HARD TEMPLATE FOR UV IMPRINTING

APPLICATION NUMBER: 10782187 FILING DATE: 02/15/2006
ISSUE DATE: 03/28/2006 FILING DATE: 02/19/2004 TITLE: METHOD AND SYSTEM TO MEASURE CHARACTERISTICS OF A FILM DISPOSED ON A SUBSTRATE

APPLICATION NUMBER: 10895214 FILING DATE: 07/20/2004 PATENT NUMBER: 7785526 ISSUE DATE: 08/31/2010

TITLE: IMPRINT ALIGNMENT METHOD, SYSTEM, AND TEMPLATE

APPLICATION NUMBER: 10789319 FILING DATE: 02/27/2004 PATENT NUMBER: 7122079 ISSUE DATE: 10/17/2006 TITLE: COMPOSITION FOR AN ETCHING MASK COMPRISING A SILICON-CONTAINING MATERIAL

APPLICATION NUMBER: 10735110 FILING DATE: 12/12/2003 PATENT NUMBER: 7323130 FILING DATE: 01/29/2008 TITLE: MAGNIFICATION CORRECTION EMPLOYING OUT-OF-PLANE DISTORTION OF A SUBSTRATE

APPLICATION NUMBER: 10917761 FILING DATE: 08/13/2004 PATENT NUMBER: 7309225 ISSUE DATE: 12/18/2007 TITLE: MOAT SYSTEM FOR AN IMPRINT LITHOGRAPHY TEMPLATE

APPLICATION NUMBER: 10917563 FILING DATE: 08/13/2004 PATENT NUMBER: 7105452 ISSUE DATE: 09/12/2006 TITLE: METHOD OF PLANARIZING A SEMICONDUCTOR SUBSTRATE WITH AN ETCHING CHEMISTRY

APPLICATION NUMBER: 10868683 FILING DATE: 06/15/2004 PATENT NUMBER: 7252715 ISSUE DATE: 08/07/2007

TITLE: SYSTEM FOR DISPENSING LIQUIDS

APPLICATION NUMBER: 10863800 FILING DATE: 06/08/2004 PATENT NUMBER: 7036389 ISSUE DATE: 05/02/2006 TITLE: SYSTEM FOR DETERMINING CHARACTERISTICS OF SUBSTRATES EMPLOYING FLUID GEOMETRIES

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APPLICATION NUMBER: 10864591 FILING DATE: 06/09/2004 PATENT NUMBER: 6982783 FILING DATE: 01/03/2006

TITLE: CHUCKING SYSTEM FOR MODULATING SHAPES OF SUBSTRATES

APPLICATION NUMBER: 10951014 FILING DATE: 09/27/2004 ISSUE DATE: 07/17/2007 PATENT NUMBER: 7244386 TITLE: METHOD OF COMPENSATING FOR A VOLUMETRIC SHRINKAGE OF A MATERIAL DISPOSED UPON A SUBSTRATE TO FORM A SUBSTANTIALLY PLANAR STRUCTURE THEREFROM

APPLICATION NUMBER: 10946565 FILING DATE: 09/21/2004 PATENT NUMBER: 7252777 ISSUE DATE: 08/07/2007

TITLE: METHOD OF FORMING AN IN-SITU RECESSED STRUCTURE

APPLICATION NUMBER: 10946159 FILING DATE: 09/21/2004 PATENT NUMBER: 7041604 ISSUE DATE: 05/09/2006 TITLE: METHOD OF PATTERNING SURFACES WHILE PROVIDING GREATER CONTROL OF RECESS ANISOTROPY

APPLICATION NUMBER: 11184664
PATENT NUMBER: 7256131 FILING DATE: 07/19/2005 ISSUE DATE: 08/14/2007 TITLE: METHOD OF CONTROLLING THE CRITICAL DIMENSION OF STRUCTURES FORMED ON A SUBSTRATE

APPLICATION NUMBER: 10919062 FILING DATE: 08/16/2007 FILING DATE: 08/16/2004 TITLE: COMPOSITION TO PROVIDE A LAYER WITH UNIFORM ETCH

CHARACTERISTICS

APPLICATION NUMBER: 10919224 FILING DATE: 08/16/2004 PATENT NUMBER: 7939131 ISSUE DATE: 05/10/2011 TITLE: METHOD TO PROVIDE A LAYER WITH UNIFORM ETCH CHARACTERISTICS

APPLICATION NUMBER: 10923628 FILING DATE: 08/20/2004 PATENT NUMBER: 6990870 ISSUE DATE: 01/31/2006 TITLE: SYSTEM FOR DETERMINING CHARACTERISTICS OF SUBSTRATES EMPLOYING FLUID GEOMETRIES

APPLICATION NUMBER: 10946577
PATENT NUMBER: 7241395 FILING DATE: 09/21/2004 ISSUE DATE: 07/10/2007 TITLE: REVERSE TONE PATTERNING ON SURFACES HAVING SURFACE PLANARITY

PERTURBATIONS

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APPLICATION NUMBER: 10946566 FILING DATE: 09/21/2004 PATENT NUMBER: 7547504 ISSUE DATE: 06/16/2009

TITLE: PATTERN REVERSAL EMPLOYING THICK RESIDUAL LAYERS

APPLICATION NUMBER: 10946570 FILING DATE: 09/21/2004
PATENT NUMBER: 7186656 ISSUE DATE: 03/06/2007
TITLE: METHOD OF FORMING A RECESSED STRUCTURE EMPLOYING A REVERSE
TONE PROCESS

APPLICATION NUMBER: 10946574 FILING DATE: 09/21/2004
PATENT NUMBER: 7205244 ISSUE DATE: 04/17/2007
TITLE: PATTERNING SUBSTRATES EMPLOYING MULTI-FILM LAYERS DEFINING
ETCH-DIFFERENTIAL INTERFACES

APPLICATION NUMBER: 11108208 FILING DATE: 04/18/2005 PATENT NUMBER: 7635445 FILING DATE: 12/22/2009

TITLE: METHOD OF SEPARATING A MOLD FROM A SOLIDIFIED LAYER DISPOSED ON A SUBSTRATE

APPLICATION NUMBER: 11000331 FILING DATE: 11/30/2004
PATENT NUMBER: 7292326 ISSUE DATE: 11/06/2007
TITLE: INTERFEROMETRIC ANALYSIS FOR THE MANUFACTURE OF NANO-SCALE
DEVICES

APPLICATION NUMBER: 11000321 FILING DATE: 11/30/2004
PATENT NUMBER: 7630067 ISSUE DATE: 12/08/2009
TITLE: INTERFEROMETRIC ANALYSIS METHOD FOR THE MANUFACTURE OF NANOSCALE DEVICES

APPLICATION NUMBER: 11047428 FILING DATE: 01/31/2005 PATENT NUMBER: 7798801 FILING DATE: 09/21/2010

TITLE: CHUCKING SYSTEM FOR NANO-MANUFACTURING

APPLICATION NUMBER: 11047499 FILING DATE: 01/31/2005 PATENT NUMBER: 7636999 ISSUE DATE: 12/29/2009 TITLE: METHOD OF RETAINING A SUBSTRATE TO A WAFER CHUCK

APPLICATION NUMBER: 11142839 FILING DATE: 06/01/2005
PATENT NUMBER: 7170589 FILING DATE: 06/01/2005
TITLE: APPARATUS TO VARY DIMENSIONS OF A SUBSTRATE DURING NANO-

SCALE MANUFACTURING

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APPLICATION NUMBER: 11101140 FILING DATE: 04/07/2005 PATENT NUMBER: 7811505 ISSUE DATE: 10/12/2010

TITLE: METHOD FOR FAST FILLING OF TEMPLATES FOR IMPRINT LITHOGRAPHY

USING ON TEMPLATE DISPENSE

APPLICATION NUMBER: 11101139 FILING DATE: 04/07/2005
PATENT NUMBER: 7281919 ISSUE DATE: 10/16/2007
TITLE: SYSTEM FOR CONTROLLING A VOLUME OF MATERIAL ON A MOLD

APPLICATION NUMBER: 11068171 FILING DATE: 02/28/2005
PATENT NUMBER: 7307118 ISSUE DATE: 12/11/2007
TITLE: COMPOSITION TO REDUCE ADHESION BETWEEN A CONFORMABLE REGION AND A MOLD

APPLICATION NUMBER: 11142808 FILING DATE: 06/01/2005
PATENT NUMBER: 7298456 ISSUE DATE: 11/20/2007
TITLE: SYSTEM FOR VARYING DIMENSIONS OF A SUBSTRATE DURING

NANOSCALE MANUFACTURING

APPLICATION NUMBER: 11126946 FILING DATE: 05/11/2005
PATENT NUMBER: 7338275 ISSUE DATE: 03/04/2008
TITLE: FORMATION OF DISCONTINUOUS FILMS DURING AN IMPRINT

LITHOGRAPHY PROCESS

APPLICATION NUMBER: 11127041 FILING DATE: 05/11/2005 PATENT NUMBER: 7727453 FILING DATE: 06/01/2010

TITLE: STEP AND REPEAT IMPRINT LITHOGRAPHY PROCESSES

APPLICATION NUMBER: 11142834 FILING DATE: 06/01/2005
PATENT NUMBER: 7420654 ISSUE DATE: 09/02/2008
TITLE: METHOD OF VARYING DIMENSIONS OF A SUBSTRATE DURING NANOSCALE MANUFACTURING

APPLICATION NUMBER: 11231616 FILING DATE: 09/21/2005
PATENT NUMBER: 7316554 ISSUE DATE: 01/08/2008
TITLE: SYSTEM TO CONTROL AN ATMOSPHERE BETWEEN A BODY AND A

SUBSTRATE

APPLICATION NUMBER: 11211766 FILING DATE: 08/25/2005
PATENT NUMBER: 7665981 ISSUE DATE: 02/23/2010
TITLE: SYSTEM TO TRANSFER A TEMPLATE TRANSFER BODY BETWEEN A MOTION

STAGE AND A DOCKING PLATE

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APPLICATION NUMBER: 11142838 FILING DATE: 06/01/2005 PATENT NUMBER: 7387508 FILING DATE: 06/17/2008

TITLE: COMPLIANT DEVICE FOR NANO-SCALE MANUFACTURING

APPLICATION NUMBER: 11292568 FILING DATE: 12/01/2005
PATENT NUMBER: 7803308 ISSUE DATE: 09/28/2010
TITLE: TECHNIQUE FOR SEPARATING A MOLD FROM SOLIDIFIED IMPRINTING
MATERIAL

APPLICATION NUMBER: 11240708 FILING DATE: 09/30/2005 PATENT NUMBER: 7259102 ISSUE DATE: 08/21/2007 TITLE: ETCHING TECHNIQUE TO PLANARIZE A MULTI-LAYER STRUCTURE

APPLICATION NUMBER: 11187406 FILING DATE: 07/22/2005 PATENT NUMBER: 7759407 ISSUE DATE: 07/20/2010

TITLE: COMPOSITION FOR ADHERING MATERIALS TOGETHER

APPLICATION NUMBER: 11231580 FILING DATE: 09/21/2005
PATENT NUMBER: 7670534 ISSUE DATE: 03/02/2010
TITLE: METHOD TO CONTROL AN ATMOSTPHERE BETWEEN A BODY AND A
SUBSTRATE

APPLICATION NUMBER: 11244428 FILING DATE: 10/05/2005 PATENT NUMBER: 7837921 ISSUE DATE: 11/23/2010 TITLE: METHOD OF PROVIDING DESIRABLE WETTING AND RELEASE

CHARACTERSTICS BETWEEN A MOLD AND A POLYMERIZABLE COMPOSITION

APPLICATION NUMBER: 11298244 FILING DATE: 12/09/2005
PATENT NUMBER: 7279113 ISSUE DATE: 10/09/2007
TITLE: METHOD OF FORMING A COMPLIANT TEMPLATE FOR UV IMPRINTING

APPLICATION NUMBER: 11292394 FILING DATE: 11/30/2005
PATENT NUMBER: 7357876 ISSUE DATE: 04/15/2008
TITLE: ELIMINATING PRINTABILITY OF SUB-RESOLUTION DEFECTS IN
IMPRINT LITHOGRAPHY

APPLICATION NUMBER: 11303777 FILING DATE: 12/16/2005 PATENT NUMBER: 7906058 ISSUE DATE: 03/15/2011

TITLE: BIFURCATED CONTACT PRINTING TECHNIQUE

APPLICATION NUMBER: 11389731 FILING DATE: 03/27/2006 PATENT NUMBER: 7224443 ISSUE DATE: 05/29/2007

TITLE: IMPRINT LITHOGRAPHY SUBSTRATE PROCESSING TOOL FOR MODULATING

SHAPES OF SUBSTRATES

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APPLICATION NUMBER: 10136188 FILING DATE: 05/01/2002 PATENT NUMBER: 7037639 ISSUE DATE: 05/02/2006

TITLE: METHODS OF MANUFACTURING A LITHOGRAPHY TEMPLATE

APPLICATION NUMBER: 11560928 FILING DATE: 11/17/2006 PATENT NUMBER: 7261831 FILING DATE: 08/28/2007

TITLE: POSITIVE TONE BI-LAYER IMPRINT LITHOGRAPHY METHOD

APPLICATION NUMBER: 11508765 FILING DATE: 08/23/2006
PATENT NUMBER: 7906180 ISSUE DATE: 03/15/2011
TITLE: COMPOSITION FOR AN ETCHING MASK COMPRISING A SILICONCONTAINING MATERIAL

APPLICATION NUMBER: 11470829 FILING DATE: 09/07/2006
PATENT NUMBER: 7491637 FILING DATE: 02/17/2009

TITLE: FORMATION OF CONDUCTIVE TEMPLATES EMPLOYING INDIUM TIN OXIDE

APPLICATION NUMBER: 11565393 FILING DATE: 11/30/2006
PATENT NUMBER: 7691313 ISSUE DATE: 04/06/2010
TITLE: METHOD FOR EXPELLING GAS POSITIONED BETWEEN A SUBSTRATE AND A MOLD

APPLICATION NUMBER: 11565350 FILING DATE: 11/30/2006
PATENT NUMBER: 7670529 ISSUE DATE: 03/02/2010
TITLE: METHOD AND SYSTEM FOR DOUBLE-SIDED PATTERNING OF SUBSTRATES

APPLICATION NUMBER: 11625082 FILING DATE: 01/19/2007 PATENT NUMBER: 7670530 FILING DATE: 03/02/2010

TITLE: PATTERNING SUBSTRATES EMPLOYING MULTIPLE CHUCKS

APPLICATION NUMBER: 11611287 FILING DATE: 12/15/2006
PATENT NUMBER: 7323417 ISSUE DATE: 01/29/2008
TITLE: METHOD OF FORMING A RECESSED STRUCTURE EMPLOYING A REVERSE
TONE PROCESS

APPLICATION NUMBER: 11690480 FILING DATE: 03/23/2007 PATENT NUMBER: 7635263 ISSUE DATE: 12/22/2009 TITLE: CHUCKING SYSTEM COMPRISING AN ARRAY OF FLUID CHAMBERS

APPLICATION NUMBER: 11669569 FILING DATE: 01/31/2007
PATENT NUMBER: 7699598 ISSUE DATE: 04/20/2010
TITLE: CONFORMING TEMPLATE FOR PATTERNING LIQUIDS DISPOSED ON SUBSTRATES

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APPLICATION NUMBER: 11695850 FILING DATE: 04/03/2007
PATENT NUMBER: 7780893 ISSUE DATE: 08/24/2010
TITLE: METHOD OF CONCURRENTLY PATTERNING A SUBSTRATE HAVING A
PLURALITY OF FIELDS AND A PLURALITY OF ALIGNMENT MARKS

APPLICATION NUMBER: 11693236 FILING DATE: 03/29/2007
PATENT NUMBER: 7547398 ISSUE DATE: 06/16/2009
TITLE: SELF-ALIGNED PROCESS FOR FABRICATING IMPRINT TEMPLATES
CONTAINING VARIOUSLY ETCHED FEATURES

APPLICATION NUMBER: 11695263 FILING DATE: 04/02/2007 PATENT NUMBER: 7462028 ISSUE DATE: 12/09/2008

TITLE: PARTIAL VACUUM ENVIRONMENT IMPRINTING

APPLICATION NUMBER: 11694500 FILING DATE: 03/30/2007
PATENT NUMBER: 7802978 ISSUE DATE: 09/28/2010
TITLE: IMPRINTING OF PARTIAL FIELDS AT THE EDGE OF THE WAFER

APPLICATION NUMBER: 11737301 FILING DATE: 04/19/2007 PATENT NUMBER: 7854867 FILING DATE: 12/21/2010

TITLE: METHOD FOR DETECTING A PARTICLE IN A NANOIMPRINT LITHOGRAPHY SYSTEM

APPLICATION NUMBER: 11749909 FILING DATE: 05/17/2007
PATENT NUMBER: 7641840 ISSUE DATE: 01/05/2010
TITLE: METHOD FOR EXPELLING GAS POSITIONED BETWEEN A SUBSTRATE AND A MOLD

APPLICATION NUMBER: 11762378 FILING DATE: 06/13/2007 PATENT NUMBER: 7473090 ISSUE DATE: 01/06/2009

TITLE: IMPRINT LITHOGRAPHY TEMPLATE TO FACILITATE CONTROL OF LIQUID

MOVEMENT

APPLICATION NUMBER: 10191749 FILING DATE: 07/09/2002 PATENT NUMBER: 6926929 FILING DATE: 08/09/2005

TITLE: SYSTEM AND METHOD FOR DISPENSING LIQUIDS

APPLICATION NUMBER: 11844824 FILING DATE: 08/24/2007 PATENT NUMBER: 7670953 ISSUE DATE: 03/02/2010

TITLE: POSITIVE TONE BI-LAYER METHOD

APPLICATION NUMBER: 11943907 FILING DATE: 11/21/2007 PATENT NUMBER: 7906274 ISSUE DATE: 03/15/2011 TITLE: METHOD OF CREATING A TEMPLATE EMPLOYING A LIFT-OFF PROCESS

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APPLICATION NUMBER: 12175258 FILING DATE: 07/17/2008
PATENT NUMBER: 7837907 ISSUE DATE: 11/23/2010
TITLE: ALIGNMENT SYSTEM AND METHOD FOR A SUBSTRATE IN A NANO-

IMPRINT PROCESS

APPLICATION NUMBER: 10194411 FILING DATE: 07/11/2002 PATENT NUMBER: 6932934 FILING DATE: 08/23/2005

TITLE: FORMATION OF DISCONTINUOUS FILMS DURING AN IMPRINT

LITHOGRAPHY PROCESS

APPLICATION NUMBER: 11858687 FILING DATE: 09/20/2007
PATENT NUMBER: 7845931 ISSUE DATE: 12/07/2010
TITLE: POLYMERIZATION TECHNIQUE TO ATTENUATE OXYGEN INHIBITION OF SOLIDIFICATION OF LIQUIDS AND COMPOSITION THEREFOR

APPLICATION NUMBER: 10194991 FILING DATE: 07/11/2002 PATENT NUMBER: 7077992 ISSUE DATE: 07/18/2006

TITLE: STEP AND REPEAT IMPRINT LITHOGRAPHY PROCESSES

APPLICATION NUMBER: 10194414 FILING DATE: 07/11/2002 PATENT NUMBER: 6900881 FILING DATE: 05/31/2005

TITLE: STEP AND REPEAT IMPRINT LITHOGRAPHY SYSTEMS

APPLICATION NUMBER: 12026049 FILING DATE: 02/05/2008 PATENT NUMBER: 7708926 ISSUE DATE: 05/04/2010

TITLE: CAPILLARY IMPRINTING TECHNIQUE

APPLICATION NUMBER: 12182905 FILING DATE: 07/30/2008 PATENT NUMBER: 7795132 FILING DATE: 09/14/2010

TITLE: SELF-ALIGNED CROSS-POINT MEMORY FABRICATION

APPLICATION NUMBER: 10194410 FILING DATE: 07/11/2002 PATENT NUMBER: 6908861 ISSUE DATE: 06/21/2005 TITLE: METHOD FOR IMPRINT LITHOGRAPHY USING AN ELECTRIC FIELD

APPLICATION NUMBER: 10227105 FILING DATE: 08/23/2002 PATENT NUMBER: 7071088 ISSUE DATE: 07/04/2006

TITLE: METHOD FOR FABRICATING BULBOUS-SHAPED VIAS

APPLICATION NUMBER: 10210785 FILING DATE: 08/01/2002 PATENT NUMBER: 7027156 FILING DATE: 04/11/2006

TITLE: SCATTEROMETRY ALIGNMENT FOR IMPRINT LITHOGRAPHY

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APPLICATION NUMBER: 10210894 FILING DATE: 08/01/2002 PATENT NUMBER: 7070405 ISSUE DATE: 07/04/2006

TITLE: ALIGNMENT SYSTEMS FOR IMPRINT LITHOGRAPHY

APPLICATION NUMBER: 10210780 FILING DATE: 08/01/2002 PATENT NUMBER: 6916584 FILING DATE: 07/12/2005

TITLE: ALIGNMENT METHODS FOR IMPRINT LITHOGRAPHY

APPLICATION NUMBER: 10235314 FILING DATE: 09/05/2002
PATENT NUMBER: 6936194 ISSUE DATE: 08/30/2005
TITLE: FUNCTIONAL PATTERNING MATERIAL FOR IMPRINT LITHOGRAPHY
PROCESSES

APPLICATION NUMBER: 10318365 FILING DATE: 12/12/2002
PATENT NUMBER: 6871558 ISSUE DATE: 03/29/2005
TITLE: METHOD FOR DETERMINING CHARACTERISTICS OF SUBSTRATE
EMPLOYING FLUID GEOMETRIES

APPLICATION NUMBER: 12389673 FILING DATE: 02/20/2009 PATENT NUMBER: 7785096 ISSUE DATE: 08/31/2010

TITLE: ENHANCED MULTI CHANNEL ALIGNMENT

APPLICATION NUMBER: 12430428 FILING DATE: 04/27/2009
PATENT NUMBER: 7927541 ISSUE DATE: 04/19/2011
TITLE: FULL-WAFER OR LARGE AREA IMPRINTING WITH MULTIPLE SEPARATED
SUB-FIELDS FOR HIGH THROUGHPUT LITHOGRAPHY

APPLICATION NUMBER: 10293223 FILING DATE: 11/13/2002
PATENT NUMBER: 6929762 ISSUE DATE: 08/16/2005
TITLE: METHOD OF REDUCING PATTERN DISTORTIONS DURING IMPRINT
LITHOGRAPHY PROCESSES

APPLICATION NUMBER: 10293224 FILING DATE: 11/13/2002
PATENT NUMBER: 7019819 ISSUE DATE: 03/28/2006
TITLE: CHUCKING SYSTEM FOR MODULATING SHAPES OF SUBSTRATES

APPLICATION NUMBER: 12576030 FILING DATE: 10/08/2009
PATENT NUMBER: 7880872 ISSUE DATE: 02/01/2011
TITLE: INTERFEROMETRIC ANALYSIS METHOD FOR THE MANUFACTURE OF NANO-SCALE DEVICES

APPLICATION NUMBER: 12605848 FILING DATE: 10/26/2009
PATENT NUMBER: 7874831 ISSUE DATE: 01/25/2011
TITLE: TEMPLATE HAVING A SILICON NITRIDE, SILICON CARBIDE OR
SILICON OXYNITRIDE FILM

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APPLICATION NUMBER: 10316963 FILING DATE: 12/11/2002 PATENT NUMBER: 6980282 FILING DATE: 12/27/2005

TITLE: METHOD FOR MODULATING SHAPES OF SUBSTRATES

APPLICATION NUMBER: 12688190 FILING DATE: 01/15/2010 PATENT NUMBER: 7931846 ISSUE DATE: 04/26/2011 TITLE: METHOD TO CONTROL AN ATMOSPHERE BETWEEN A BODY AND A

SUBSTRATE

APPLICATION NUMBER: 12689773 FILING DATE: 01/19/2010 PATENT NUMBER: 7858528 ISSUE DATE: 12/28/2010

TITLE: POSITIVE TONE BI-LAYER METHOD

APPLICATION NUMBER: 10293919 FILING DATE: 11/13/2002 PATENT NUMBER: 7132225 ISSUE DATE: 11/07/2006

TITLE: METHODS OF INSPECTING A LITHOGRAPHY TEMPLATE

APPLICATION NUMBER: 12707365 FILING DATE: 02/17/2010 PATENT NUMBER: 7910042 ISSUE DATE: 03/22/2011

TITLE: CAPILLARY IMPRINTING TECHNIQUE

APPLICATION NUMBER: 12762658 FILING DATE: 04/19/2010 PATENT NUMBER: 7943081 FILING DATE: 05/17/2011

TITLE: STEP AND REPEAT IMPRINT LITHOGRAPHY PROCESSES

APPLICATION NUMBER: 10375817 FILING DATE: 02/27/2003
PATENT NUMBER: 7452574 ISSUE DATE: 11/18/2008
TITLE: METHOD TO REDUCE ADHESION BETWEEN A POLYMERIZABLE LAYER AND A SUBSTRATE EMPLOYING A FLUORINE-CONTAINING LAYER

APPLICATION NUMBER: 12946063 FILING DATE: 11/15/2010 PATENT NUMBER: 7947608 FILING DATE: 05/24/2011

TITLE: POSITIVE TONE BI-LAYER METHOD

APPLICATION NUMBER: 10438224 FILING DATE: 05/14/2003
PATENT NUMBER: 6805054 ISSUE DATE: 10/19/2004
TITLE: METHOD, SYSTEM AND HOLDER FOR TRANSFERRING TEMPLATES DURING
IMPRINT LITHOGRAPHY PROCESSES

APPLICATION NUMBER: 10396615 FILING DATE: 03/25/2003 PATENT NUMBER: 7179396 ISSUE DATE: 02/20/2007

TITLE: POSITIVE TONE BI-LAYER IMPRINT LITHOGRAPHY METHOD

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APPLICATION NUMBER: 10423642 FILING DATE: 04/25/2003
PATENT NUMBER: 7396475 ISSUE DATE: 07/08/2008
TITLE: METHOD OF FORMING STEPPED STRUCTURES EMPLOYING IMPRINT
LITHOGRAPHY

APPLICATION NUMBER: 10437476 FILING DATE: 05/14/2003
PATENT NUMBER: 6951173 ISSUE DATE: 10/04/2005
TITLE: ASSEMBLY AND METHOD FOR TRANSFERRING IMPRINT LITHOGRAPHY
TEMPLATES

APPLICATION NUMBER: 10645306 FILING DATE: 08/21/2003 PATENT NUMBER: 7442336 FILING DATE: 10/28/2008

TITLE: CAPILLARY IMPRINTING TECHNIQUE

APPLICATION NUMBER: 10614716 FILING DATE: 07/07/2003
PATENT NUMBER: 7179079 ISSUE DATE: 02/20/2007
TITLE: CONFORMING TEMPLATE FOR PATTERNING LIQUIDS DISPOSED ON SUBSTRATES

APPLICATION NUMBER: 10616294 FILING DATE: 07/09/2003
PATENT NUMBER: 7150622 ISSUE DATE: 12/19/2006
TITLE: SYSTEMS FOR MAGNIFICATION AND DISTORTION CORRECTION FOR IMPRINT LITHOGRAPHY PROCESSES

APPLICATION NUMBER: 10898034 FILING DATE: 07/23/2004
PATENT NUMBER: 7531025 ISSUE DATE: 05/12/2009
TITLE: METHOD OF CREATING A TURBULENT FLOW OF FLUID BETWEEN A MOLD
AND A SUBSTRATE

APPLICATION NUMBER: 10898037 FILING DATE: 07/23/2004
PATENT NUMBER: 7270533 ISSUE DATE: 09/18/2007
TITLE: SYSTEM FOR CREATING A TURBULENT FLOW OF FLUID BETWEEN A MOLD AND A SUBSTRATE

APPLICATION NUMBER: 11695469 FILING DATE: 04/02/2007
PATENT NUMBER: 7768624 ISSUE DATE: 08/03/2010
TITLE: METHOD FOR OBTAINING FORCE COMBINATIONS FOR TEMPLATE
DEFORMATION USING NULLSPACE AND METHODS OPTIMIZATION
TECHNIQUES

APPLICATION NUMBER: 12392663 FILING DATE: 02/25/2009
PATENT NUMBER: 7815824 ISSUE DATE: 10/19/2010
TITLE: REAL TIME IMPRINT PROCESS DIAGNOSTICS FOR DEFECTS

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APPLICATION NUMBER: 10687562 FILING DATE: 10/16/2003
PATENT NUMBER: 7261830 ISSUE DATE: 08/28/2007
TITLE: APPLYING IMPRINTING MATERIAL TO SUBSTRATES EMPLOYING

ELECTROMAGNETIC FIELDS

APPLICATION NUMBER: 10677639 FILING DATE: 10/02/2003 PATENT NUMBER: 7090716 ISSUE DATE: 08/15/2006

TITLE: SINGLE PHASE FLUID IMPRINT LITHOGRAPHY METHOD

APPLICATION NUMBER: 10463396 FILING DATE: 06/17/2003
PATENT NUMBER: 7157036 ISSUE DATE: 01/02/2007
TITLE: METHOD TO REDUCE ADHESION BETWEEN A CONFORMABLE REGION AND A PATTERN OF A MOLD

APPLICATION NUMBER: 10694284 FILING DATE: 10/27/2003 PATENT NUMBER: 7122482 FILING DATE: 10/17/2006

TITLE: METHODS FOR FABRICATING PATTERNED FEATURES UTILIZING IMPRINT

LITHOGRAPHY

MARY BENTON, EXAMINER
ASSIGNMENT SERVICES BRANCH
PUBLIC RECORDS DIVISION

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PATENT ASSIGNMENT

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SUBMISSION TYPE:	NEW ASSIGNMENT	
NATURE OF CONVEYANCE:	ASSIGNMENT	
CONVEYING PARTY DATA		
N	lame	Execution Date
Molecular Imprints, Inc.		09/01/2011
RECEIVING PARTY DATA		

Name:	Canon Inc.	
Street Address:	30-2 Shimomaruko 3-chome	
City:	Ohta-ku, Tokyo	
State/Country:	JAPAN	
Postal Code:	146-8501	

PROPERTY NUMBERS Total: 110

Property Type	Number
Patent Number:	7136150
Patent Number:	7140861
Patent Number:	7019835
Patent Number:	7785526
Patent Number:	7122079
Patent Number:	7323130
Patent Number:	7309225
Patent Number:	7105452
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Patent Number:	7244386
Patent Number:	7252777
Patent Number:	7041604
Patent Number:	7256131

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Patent Number:	7798801
Patent Number:	7636999
Patent Number:	7170589
Patent Number:	7811505
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Patent Number:	7727453
Patent Number:	7420654
Patent Number:	7316554
Patent Number:	7665981
Patent Number:	7387508
Patent Number:	7803308
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Patent Number:	7759407
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Patent Number:	7396475
Patent Number:	6951173
Patent Number:	7442336
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Patent Number:	7150622
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Patent Number:	7270533
Patent Number:	7768624
Patent Number:	7815824
Patent Number:	7261830
Patent Number:	7090716
Patent Number:	7157036
Patent Number:	7122482

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ATTORNEY DOCKET NUMBER: 093155.010200

NAME OF CHRAITTED

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	Shoba Jaglal
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